QUALITY CONTROL ISSUES IN SEMICONDUCTOR MANUFACTURING

JULY 25 – JULY 26
9:00 AM – 6:00 PM

This workshop will equip metrology professionals with the skills to leverage cutting-edge Transmission Electron Microscopy (TEM) for the semiconductor industry's pursuit of 1 nm microchips. Attendees will gain hands-on experience analyzing real-world samples using the advanced Talos F200i TEM, with a focus on the critical role of precise sample preparation for high-resolution analysis. Beyond TEM, the workshop will explore a suite of complementary analytical techniques, including UV-Vis spectroscopy, X-ray diffraction (XRD), electron paramagnetic resonance (EPR), and photoluminescence (PL). These powerful tools empower participants to develop robust strategies for preventing, detecting, and controlling material defects - a key driver of performance optimization and innovation in semiconductor technology.

Location: Flagstaff Arizona

Discounted Housing Options Available

Course Instructors

- **Dr Miguel Jose Yacaman,** Regent's Professor of NAU's Applied and Materials Science department and pioneer in nanotechnology
- **Dr. Domingo Garcia,** Professor, at Autonomous University of Nuevo León
- **Dr. Andy Wang, P**rofessor & Director of the NAU Metrology Research and Teaching Laboratory

Register @: https://forms.gle/TuzG451wEmVtyDzb6

CONTACT

Questions? Contact Lauren Majure
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COST: $399

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College of Engineering, Informatics, and Applied Sciences